

Title (en)

A chemical mechanical polishing pad having window with integral identification feature

Title (de)

Chemisch-mechanisches Polierpad mit Fenster mit integrierter Identifizierungsfunktion

Title (fr)

Tampon à polir mécanique et chimique ayant une fenêtre avec fonction d'identification intégrale

Publication

**EP 2177312 A1 20100421 (EN)**

Application

**EP 09155069 A 20090313**

Priority

- US 25282008 A 20081016
- US 39753509 A 20090304

Abstract (en)

Chemical mechanical polishing pads having a window (16,20,120) with an integral identification feature (11,30,130), wherein the window has a polishing face and a nonpolishing face, wherein the integral identification feature is observable through the window, and wherein the integral identification feature identifies the chemical mechanical polishing pad as a type of chemical mechanical polishing pad selected from a plurality of types of chemical mechanical polishing pads. Also provided is a method of making such chemical mechanical polishing pads and for using them to polish a substrate selected from a magnetic substrate, an optical substrate and a semiconductor substrate.

IPC 8 full level

**B24B 7/22** (2006.01); **B24B 37/04** (2006.01); **B24D 13/14** (2006.01)

CPC (source: EP)

**B24B 7/228** (2013.01); **B24B 37/04** (2013.01); **B24D 13/14** (2013.01)

Citation (applicant)

- US 5533923 A 19960709 - SHAMOUILIAN SHAMOUIL [US], et al
- US 5584146 A 19961217 - SHAMOUILLAN SHAMOUIL [US], et al

Citation (search report)

- [DA] US 5533923 A 19960709 - SHAMOUILIAN SHAMOUIL [US], et al
- [A] US 2007010169 A1 20070111 - SWISHER ROBERT G [US], et al

Cited by

FR3006219A1; KR20230073888A

Designated contracting state (EPC)

DE FR

Designated extension state (EPC)

AL BA RS

DOCDB simple family (publication)

**EP 2177312 A1 20100421**; **EP 2177312 B1 20110427**; DE 602009001168 D1 20110609

DOCDB simple family (application)

**EP 09155069 A 20090313**; DE 602009001168 T 20090313